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Area-Energy Tradeoffs of Logic Wear-Leveling for BTI-induced Aging

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Logic Wear-Leveling (LWL):

 a <u>post-fabrication</u> self-adapting circuit-level approach to mitigate timing degradations.

Research Objective:

 Mitigate *Transistor Aging* due to BTI and HCI thus reducing the energy wastage due to conservative selection of guardbands.

Targeting Aging-critical Elements:

- aging-critical logic portions of the circuit are targeted for protection → minimal overhead
- power-gating is effective in reducing BTI and HCI.
 Switching activity (p) effects the shift in V_{th}

 $\Delta V_{th}(t) \propto (pt)^n$



How to leverage Dark Silicon???

area of chip which cannot be operated due to constrains of simultaneous operation of all transistors which are:

- cooling cost
- power cost





Need addressed	Approach	Benefit	
Transistor Aging	Power-gating of critical elements	Reduced lifetime delay degradation through stress reduction	
Energy Consumption	Reduced voltage guard bands	Low energy requirement with narrower margins for longer periods	
	De-emphasized role of voltage regulators	Circumvent conversion inefficiencies and switching losses	
	Selective Redundancy	Power-gating lowers the leakage energy overheads	



Related Works



Technique Anti-Aging Strategy		Design Requirements/ Parameters	Adaptability Characteristics/ Degree	Overheads		
	Anti-Aging Strategy			Throughput	Power	Area
-		Wa	orst-case Design			
VM, FM	Static Margin	$MD-RoD/ \\ \Delta V_{DD}, \\ \Delta F_{nominal}$	None	FM: High	VM: High (Dynamic & Leakage)	None
Gate-Sizing	Static Margin	MD-RoD; Extended Std. Lib.; Multi-obj. Opt./ $\Delta \beta_{i}$ \forall gates i	None	None	Medium (Dynamic & Leakage)	Low (Gate-level)
Re-Synthesis	Static Margin	MD-RoD annotated Std. Lib.; Aging-aware Synthesis/ Δβi, ΔV _{th,i} ∀ gates i	None	None	Low-Medium (Dynamic & Leakage)	Low (Gate-level)
		Dynamic	Operating Condition	ons	-	
DVFS	Dynamic Margin	Timing Sensors; Feedback Control/ $\Delta V_{DD}(t), \Delta F(t),$ $\Delta V_{bb}(t)$	Yes/ Fully Autonomous	Low	Medium (Dynamic & Leakage)	Medium (On-chip VR & sensors)
SVS	Dynamic Margin	$\frac{\text{MD-RoD}}{\Delta V_{DD}(t + \Delta t_{step})}$	Yes/ t _{step}	None	Medium (Dynamic & Leakage)	Medium (On-chip VR)
GNOMO	Static Margin + Power-Gating	MD-RoD/ (<i>V_{DD,g}, t_{idle}</i>)	None	Medium (Workload Dependent)	Medium (Dynamic & Leakage)	None
	-	Adaptive	Resource Managem	nent		
SD	Proactive Mngt. + Power-Gating	Modular Redundancy/ Sleep Interval	Yes/ Sleep Interval	None	High (Leakage)	High (Module- level)
ITL schemes	Proactive Mngt. + Power-Gating	Exploit App. Redundancy/ Idle time	Yes/ Task Scheduling	Medium (Workload Dependent)	None	None
LWL	Proactive Fine- Grain Mngt. + Power-Gating	CPRT/ Sleep Interval	Yes/ Sleep Interval	None	Minimal (Leakage)	Low (Gate-level)
RR	Proactive Fine- Grain Mngt. + Power-Gating	Timing Sensors; Feedback Control; CPRT/ ERT%	Yes/ Fully Autonomous	None	Minimal (Leakage)	Low (Gate-level & sensors)

Proposed herein

CF-2016

slide 4







3) LWL covers logic paths having delays:

$$[D_{critical}(t) * (100\% - P), D_{critical}(t)]$$

- P is top-path parameter
- based on near critical paths due to aging and/or PV effects
- P=10% used herein







Circuit After Critical Path Replication





LWL: Proactive resource switching to balance stress among replicated components.







NanGate Library based on 45nm Predictive Technology Model is used. Built-in models for BTI and HCI are utilized for HSPICE simulations







Delay degradation (% inc in delay from initial time) over a lifetime of 10 years.







Delay reduction factors are calculated by taking the ratio of VM's degradation and LWL's degradation.

The reduction factors are seen to correlate with the energy savings achieved.



→ 3 yr guardband reduction → 10 yr guardband reduction





Implications of reducing delay headroom towards that of a baseline circuit operating at nominal voltage





Area Overhead w.r.t. Related Works



Case-study:

- 45nm-based Intel Penryn multicore processor
- based on [9], 46.1% of total die area is considered as Core-area

Execution unit:

- only 39.03% of a single core area is occupied by execution unit
- 65.5% of execution unit can be considered as aging-critical portion
 → aging-critical portion = 11.7% of die

Area cost:

- SD and BubbleWrap: 4.36% to 23.03%
- LWL: 0.79% to 2.7%
- For BubbleWrap: half of the cores are designated as *expandable*
- For SD: aging-sensitive logic is replicated
- For LWL: utilization model with P = 7% of paths in arithmetic unit







Summary of Approach

- LWL provides an adaptive technique for anti-aging using a spatial redundancy and power-gating to enable BTI recovery
- Accurate aging modeling → unnecessary

as circuit degradation is determined using operational conditions

- LWL is shown to successfully reduce the guardband with delay reductions ranging from 1.92-fold to 2.84-fold over nominal values with 5% timing margin
- Favorable energy savings as high as 31.98% with 0% timing margin are obtained due to further reduction of operating voltage
- Area cost is traded for energy reduction by minimizing ΔV_{th}
- Dark silicon effect has inspired us to allocate unused space to reduce aging impact in critical region of circuit
 - reduce energy consumption,
 - avoid need for precise aging models, and
 - intrinsically accommodate the process variation within the actual asbuilt circuits



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